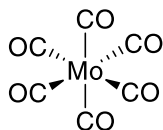


Catalog # 42-1350 Molybdenum carbonyl, 98%



Thermal Behavior:

- Melting point: 150-151°C,
- Boiling point: 156°C
- Vapor pressure: 20°C/~0.097 Torr; 40°C/0.8 Torr [1, 3]

Technical Notes:

1. ALD precursor used for Mo thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
MoN _x	ALD PEALD	40°C	-	NH ₃	225°C 180-300°C	2-3
MoO ₃	ALD PEALD	RT	2.6 Torr -	H ₂ O, O ₃ O ₂	152-172°C 162°C	4-5
MoS ₂	ALD PEALD	RT, 40°C	1.3-3.3 Torr 0.5 Torr	M ₂ S ₂ H ₂ S	100°C 175-225°C	6-8
MoSe ₂	ALD	55°C	-	(Me ₃ Si ₂)Se	167°C	9
MoO _x :N	ALD	RT	1 Torr	O ₃ , NH ₃	170°C	10

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